Title (en)

APPARATUS FOR CONDITIONING A POLISHING PAD

Title (de)

VORRICHTUNG ZUM ABRICHTEN EINES POLIERKISSEN

Title (fr)

APPAREIL POUR DRESSER UN PATIN DE POLISSAGE

Publication

EP 0750968 B1 20000216 (EN)

Application

EP 96304660 A 19960625

Priority

US 56495 P 19950626

Abstract (en)

[origin: EP0750968A1] A conditioning end effector apparatus (10) for conditioning a CMP polish pad (40) includes an end effector (20) for contacting CMP polish pad (40). Holder mechanism (12) includes end effector recess (18) for receiving end effector (20) . Spacer mechanism (22 or 22') is also located at predetermined locations in end effector recess (18) to associate with end effector openings (26) in end effector (20) . End effector (20) firmly attaches through spacer mechanism (22 or 22') to holder mechanism (12) using a fastening device (24). Because of spacer mechanism (22 or 22'), end effector (20) is at distance from recess face (36) to permit slurry (38) that is deposited on CMP polish pad (40) to pass through end effector openings (26). <IMAGE>

IPC 1-7

B24B 37/04

IPC 8 full level

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CPC (source: EP KR)

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